



# 제 30회 한국반도체학술대회

The 30th Korean Conference on Semiconductors

2023년 2월 13일(월) ~ 15일(수) | 강원도 하이원리조트(그랜드호텔 컨벤션타워)

2023년 2월 15일(수), 09:00-10:30

Room H (하트 I, 6층)

## B. Patterning (Lithography & Etch Technology) 분과

### [WH1-B] Advanced Etch Technology I

좌장: 채희엽 교수(성균관대학교)

<b>WH1-B-1</b> 09:00-09:30 [초청]	<b>Control of Selective Si<sub>3</sub>N<sub>4</sub> Etching for 3D NAND Manufacturing</b> Sangwoo Lim <i>Department of Chemical and Biomolecular Engineering, Yonsei University</i>
<b>WH1-B-2</b> 09:30-10:00 [초청]	<b>Leading Edge HARC Etching Technology and Hurdles of Its Extension</b> Sung-II Cho <i>Manufacturing Technology Center, Device Solutions, Samsung Electronics Co., Ltd.</i>
<b>WH1-B-3</b> 10:00-10:15	<b>Plasma Atomic Layer Etching of Molybdenum with Surface Fluorination and Ion Bombardment</b> Yongjae Kim <sup>1</sup> , Hojin Kang <sup>2</sup> , Heeju Ha <sup>2</sup> , and Heeyeop Chae <sup>1,2</sup> <i><sup>1</sup>SKKU Advanced Institute of Nanotechnology, Sungkyunkwan University, <sup>2</sup>School of Chemical Engineering, Sungkyunkwan University</i>
<b>WH1-B-4</b> 10:15-10:30	<b>Cyclic Etch Process Using Low-GWP Etchants</b> Sanghyun You <sup>1,2</sup> and Chang-Koo Kim <sup>1,2</sup> <i><sup>1</sup>Department of Chemical Engineering, Ajou University, <sup>2</sup>Department of Energy Systems Research, Ajou University</i>